

PATENT APPLICATION  
42390.P12085

**AMENDMENT**

**Amendments to the Claims**

1.(currently amended) A method comprises:

~~forming a phase shift mask having a periodic pattern of etched regions and unetched regions;~~

performing a first exposure to a photoresist layer formed on a substrate through ~~the~~ a phase shift mask having a periodic pattern of etched regions and unetched regions;

laterally offsetting the phase shift mask; and

performing a second exposure to the photoresist layer through the laterally offset phase shift mask.

2.(original) The method of Claim 1 wherein said photoresist is a negative photoresist.

3.(original) The method of Claim 1 wherein said phase shift mask is formed of quartz.

4.(original) The method of Claim 2 further comprises:

developing said negative photoresist layer; and

etching said substrate using said developed photoresist layer as a etch mask.

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5.(original) The method of Claim 1 wherein said periodic pattern is a checkerboard pattern of etched regions and unetched regions.

6.(original) The method of Claim 1 wherein said periodic pattern comprises alternating stripes of etched regions and unetched regions.

7.(original) The method of Claim 5 wherein said lateral offsetting comprises shifting said phase shift mask in both an x direction and a y direction.

8.(original) The method of Claim 7 wherein said offsetting has a magnitude less than a dimension of said etched region.

9.(original) The method of Claim 6 wherein said lateral offsetting comprises rotating said phase shift mask.

10.(original) The method of Claim 10 wherein said rotating is a ninety-degree rotation.

11.(original) The method of Claim 1 wherein said lateral offsetting comprises rotating and shifting said phase shift mask.

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12.(original) The method of Claim 1 wherein said etched regions have a portion of the phase shift mask removed to a depth sufficient to cause exposing radiation passing through to be 180 degrees out of phase with radiation passing through said unetched regions.

Claims 13-31 (withdrawn).